

SPS Europe

Description

M.M.R.C. distributes a range of POLOS spin coaters and hot plate systems from SPS in Europe. The systems are table top size units available in a number of materials.

SPS POLOS Spin Coaters

The spin coaters are available for wafers up to 150mm, 200mm and 300mm. Principal features of the base model SPIN 150i are as follows:

- ❑ Single substrate spin processor for cleaning, drying, coating, developing and/or etching up to Ø160mm substrates.
- ❑ Full-Plastic System in Natural Polypropylene (NPP).
- ❑ Table-Top Model for manual or automated (optional) chemical dispense.
- ❑ Transparent Lid with syringe holder for central dispensing.
- ❑ Automatic safety lid lock with sensor interlock.
- ❑ Detachable controller interface for easy integration.
- ❑ N2 diffuser for N2 purge during process.
- ❑ Easy, step-by-step recipe programming via large colour touchscreen.
- ❑ Unlimited Program Storage for recipes with multiple steps / each for:
 - ❑ Time 0.1-99999 sec/step.
 - ❑ Speed 0-12,000 rpm.
 - ❑ Rotation direction (CW, CCW, puddling).
 - ❑ Acceleration / Deceleration 1-30,000rpm/sec, selectable per step.
 - ❑ Vacuum On/Off.
- ❑ 3 Programmable Dry Contacts: e.g. for automated control of Dispense unit, Nitrogen diffuser, etc.
- ❑ Structured and password protected recipe storage for easy and safe management.
- ❑ Digitally controlled Motor with digital incremental speed signal feed back.



Standard included:

- ❑ (1) standard Vacuum Chuck A-V36-S45-PP-HD, Ø45mm for up to Ø6" wafers.
- ❑ (1) D-V10-S50-PP, Small Fragment Adapter.
- ❑ (for Ø½" - Ø2" Pieces and Fragments optional) (Alternative chucks optionally available).
- ❑ Drain connection 1" male NPT (Exhaust Hose optionally available)

SPS POLOS Hot Plates

The POLOS Hotplate is a quality system engineered for ease of use, low maintenance and a long lifetime by providing extremely accurate and even temperatures across a surface. Units include the 125D, 150D and the 200D models.

Features of all POLOS Hot Plates

- ❑ Temperatures from 50 – 250°C (adjustable in steps of 1°C).
- ❑ Programmable storage of 10 programs (Temperature/Time).
- ❑ Temperature Uniformity +/- 0,5 °C.
- ❑ Heater Surface Area 180 x 180 mm.
- ❑ Suitable for 1 x 6" Wafer.
- ❑ Heater Block Material: Aluminum (anodized) or PTFE coated.
- ❑ CE-Certification.
- ❑ Countdown timer (1-999 sec.) with acoustic alarm.

Applications

- ❑ Curing of photo resist.
- ❑ Curing of epoxy.
- ❑ Any work requiring precise temperature.

Options

- ❑ Optional proximity pins.
- ❑ Optional wafer lifter.
- ❑ Optional lid and N2 injection.

Purchase Information

Supporting technical product data sheets available upon request.